



INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(51) International Patent Classification ⁷ : C07D 303/48, 303/08, 301/26, 301/03, C08G 65/00, C08F 16/26		A2	(11) International Publication Number: WO 00/66575 (43) International Publication Date: 9 November 2000 (09.11.00)
(21) International Application Number: PCT/US00/11746 (22) International Filing Date: 1 May 2000 (01.05.00) (30) Priority Data: 60/132,453 4 May 1999 (04.05.99) US (71) Applicant (for all designated States except US): E.I. DU PONT DE NEMOURS AND COMPANY [US/US]; 1007 Market Street, Wilmington, DE 19898 (US). (72) Inventors; and (75) Inventors/Applicants (for US only): PETROV, Viacheslav, Alexandrovich [US/US]; 2 Cappa Court, Hockessin, DE 19707 (US). FEIRING, Andrew, Edward [US/US]; 7 Buck- ridge Drive, Wilmington, DE 19807 (US). FELDMAN, Jer- ald [US/US]; Brackenville Woods, 16 Cinnamon Drive, Hockessin, DE 19707 (US). (74) Agent: MAGEE, Thomas, H.; E.I. Du Pont De Nemours And Company, Legal Patent Records Center, 1007 Market Street, Wilmington, DE 19898 (US).		(81) Designated States: AE, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, CA, CH, CN, CR, CU, CZ, DE, DK, DM, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MD, MG, MK, MN, MW, MX, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, UA, UG, US, UZ, VN, YU, ZW, ARIPO patent (GH, GM, KE, LS, MW, SD, SL, SZ, TZ, UG, ZW), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, GW, ML, MR, NE, SN, TD, TG). Published Without international search report and to be republished upon receipt of that report.	
(54) Title: POLYFLUORINATED EPOXIDES AND ASSOCIATED POLYMERS AND PROCESSES			
(57) Abstract			
A method for producing partially fluorinated epoxides and corresponding polyether homopolymers of these polyfluorinated epoxides is described. Also described is a method for incorporating a fluoroalcohol functional group into a polymer as a pendant group. Certain perfluorinated olefins are also described. These polyfluorinated epoxides and the associated polymers and methods relating to them are useful components in photoresists, particularly in lithographic photoresists for use at low ultraviolet wavelengths (e.g., 157 nm).			